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PATENT



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

APPLICANTS: Yi Yeol LYU et al. CONF. NO.: 8277  
SERIAL NO.: 10/722,460 GROUP: 2818  
FILED: November 28, 2003 EXAMINER: Quoc Dinh Hoang  
FOR: SILOXANE-BASED RESIN AND A SEMICONDUCTOR  
INTERLAYER INSULATING FILM USING THE SAME  
DOCKET NO.: 6661-000007/US

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**RESPONSE TO RESTRICTION REQUIREMENT**

Customer Service Window  
Randolph Building  
401 Dulany Street  
Alexandria, VA 22314  
**Mail Stop Amendment**

December 30, 2005

Dear Sir:

Responsive to the Examiner's Restriction Requirement dated October 31, 2005, the due date having been extended one (1) month to December 31, 2005, the following remarks are respectfully submitted in connection with the above-referenced application.

01/03/2006 MBEYENE1 00000021 10722460

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120.00 DP

***REMARKS***

The Examiner required restriction of one of the following inventions:

Group I: claims 1-8 and 16-18, drawn to a siloxane-based resin, classified in class 257, subclass 643; and